

said spacer being in electrical contact with one of said row-directed or column-directed wires.

58. An electron beam apparatus according to claim 57, wherein said plate-shaped spacer is rectangularly parallelepiped in such a way that the longitudinal direction thereof is in parallel with one of said row-directed or column-directed wires with which said spacer is in electrical contact.

59. An electron beam apparatus according to claim 57, wherein said row-directed wires are laminated over said column-directed wires and said spacer is in electrical contact with one of said row-directed wires, or wherein said column-directed wires are laminated over said row-directed wires and said spacer is in electrical contact with one of said column-directed wires.

60. An electron beam apparatus according to claim 57, wherein said spacer has a semiconductor film on its surface.

61. An electron beam apparatus according to claim 57, wherein said apparatus further comprises a target arranged to be irradiated with an electron beam emitted from said electron-emitting devices.